[ABSTRACT]

A substrate treatment device according to the present invention is provided with: a nozzle that is arranged along an inner wall surface of a treatment container and that is provided with a gap from the inner wall surface of the treatment container at least at a lower section of said treatment container; a nozzle base section that supports the nozzle and that has, in the interior thereof, a flow passage communicating with the nozzle; a support member that is provided along the inner wall surface and that is joined to a first joining surface of the nozzle base section, said first joining surface not facing the inner wall surface; and a slope adjusting tool configured to be capable of adjusting the slope of the nozzle base section at a position displaced toward the center of the treatment container with respect to the center of gravity of a nozzle assembly including the nozzle and the nozzle base section.